EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S2	7920	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:04
S3	97	((dry cleaning) or dry$cleaning) same reactor	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 10:42
S4	9	S2 and S3	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 10:29
S5	1	("5861066").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/25 10:32
S6	1	("6884297").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/25 10:32
S7	15	("20020023588" | "20030041971" | "20030221780" | "20040149212" | "20040187780" | "5935338" | "6117244" | "6120605" | "6183563" | "6364954" | "6402848" | "6582522" | "6586343" | "6656838" | "6802906").PN. OR ("6884297"). URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/25 10:41
S9	1	("6312526").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/25 10:41
S12	21	((dry clean$3) or dry$clean$3) same reactor same dummy	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 10:43
S13	3	S2 and S12	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 11:33
S14	4	S2 and ((dummy with (wafer or semi$1conductor)) same (rf or radio frequency))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 12:46
S15	451	S2 and ((wafer or semi$1conductor) same (rf or radio frequency))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 11:40

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S17	140	S2 and ((wafer or semi$1conductor) same (rf or radio frequency) same etch$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 11:40
S18	8	S2 same (wafer or semi$1conductor) same (rf or radio frequency) same etch	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 11:43
S19	11	S2 same (wafer or semi$1conductor) same (rf or radio frequency) same etch$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 11:43
S20	7920	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 13:48
S21	0	S20 same (bcl with (ar or argon))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 13:51
S28	49	S20 and ("bcl.sub.3" with (ar or argon))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 13:54
S34	6	S20 and ((dummy (wafer or semi$1conductor)) with clean$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 15:09
S35	1	("20040014327").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/02 11:21
S36	3	S20 and ((clean with reactor) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 18:00
S37	1081	bcl$ with (ar or argon)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 18:01
S39	17	S20 and ((bcl$ with (ar or argon)) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 11:43
S40	8	gas curtain hole	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 08:58

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S41	61	(rf or (radio frequency)) with clean$3 with activat$3 with gas	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 08:59
S42	7920	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 08:59
S43	10	S41 and S42	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 08:59
S45	75	S42 and ((clean$3 with (reactor or chamber)) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:21
S46	11	S42 and ((clean$3 with (reactor or chamber)) same (rf or (radio frequency)) same (shower$1head or (shower head)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:33
S47	2	S42 and ((clean$3 with (reactor or chamber)) same ((rf or (radio frequency)) with ((shower$1head or shower) or (distribution or dispersion)) with head))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:38
S48	438	(rf or (radio frequency)) with (shower$1head or shower or distribution or dispersion) with head	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:39
S49	13	((rf or (radio frequency)) with (shower$1head or shower or distribution or dispersion) with head) same clean	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:47
S50	1	("5449410").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/26 10:47
S51	7	("4960488" | "5158644" | "6030902").PN. OR ("6305390").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/27 14:41
S52	11	(semiconductor or wafer) same ((shower$1head or (shower head)) with first with spray with hole)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/26 12:12
S54	71	clean$3.ti. and (reactor.ti. or chamber.ti.) and plasma.ti. and (semiconductor or wafer)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/26 12:16
S55	12	clean$3.ti. and (reactor.ti. or chamber.ti.) and plasma.ti. and (semiconductor or wafer) and (shower$1head or (shower head))	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/26 12:19

S56	2	clean$3.ti. and (reactor.ti. or chamber.ti.) and plasma.ti. and (semiconductor or wafer) and ((shower$1head or (shower head)) with first)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/26 12:19
S58	75	((dummy with (wafer or semi$1conductor)) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 12:48
S61	4	(dummy with (wafer or semi$1conductor)) same (rf or (radio frequency)) same (shower$1head or (shower head))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 12:49
S62	9	(dummy with (wafer or semi$1conductor)) same (rf or (radio frequency)) same (shower$1head or shower or dispersion or distribution)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 12:55
S63	951	(wafer or semi$1conductor) same (rf or (radio frequency)) same (shower$1head or shower)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 12:55
S64	15	(wafer or semi$1conductor) same (rf or (radio frequency)) same (shower$1head or shower) same ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 13:22
S65	86	(first with ((source or reaction) gas) with (hole or inject$3)) same (wafer or semiconductor) same (reactor or chamber)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 14:00
S66	1	("6,921,437").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/26 14:00
S67	19	("20020092471" | "20040050325" | "20040050326" | "20040099377" | "20040221809" | "5010842" | "5422139" | "5453124" | "5567267" | "5595606" | "5622606" | "5766364" | "5792261" | "5938333" | "6086677" | "6302964" | "6333019" | "6499425" | "6502530").PN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/26 14:17
S68	1	("6,086,677").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/26 14:59
S78	2	((rf or (radio frequency)) with power with etch$3 with rate with (increas$3 or greater)) same bcl$	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:20

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S79	4	((rf or (radio frequency)) with etch$3 with rate with (increas$3 or greater)) same bcl$	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:21
S80	19416	(rf or (radio frequency)) with (chuck or block or susceptor)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:41
S81	26	((rf or (radio frequency)) with (chuck or block or susceptor)) same S42	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:43
S82	385	((rf or (radio frequency)) with (chuck or block or susceptor)) same clean$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:43
S83	130	((rf or (radio frequency)) with (chuck or block or susceptor)) with clean$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:49
S84	2406	dummy near wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:50
S85	311	S84 with (chuck or block or susceptor)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:50
S87	2	(S84 with (chuck or block or susceptor)) same (rf or (radio frequency)) same S42	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 16:02
S88	37	(chuck or block or susceptor) same (rf or (radio frequency)) same S42	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 16:03
S90	10	bcl$ same ((test$3 or sacrific$6 or blank or dummy) near wafer) same (rf or (radio frequency)) same (ar or argon)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 16:18
S91	7941	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 08:55

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S96	174	dummy near wafer.clm.	US-PGPUB; USPAT; USOCR; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 09:02
S97	21	S91 same dummy	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 08:55
S98	13	S91 and (dummy near wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 09:47
S99	29	(in situ) near plasma near clean$3	US-PGPUB; USPAT; USOCR; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 10:27
S100	1	("6,387,185").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/27 09:04
S101	1	("5728602").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/27 09:47
S102	85	(in situ) with plasma with clean$3	US-PGPUB; USPAT; USOCR; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 13:10
S103	13	("5728602").URPN.	USPAT	ADJ	ON	2006/04/27 10:51
S104	1240	dummy substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 10:52
S105	4	S104 and S91	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 10:54
S106	226	bcl$ and S91	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 10:55

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S10 7	3	bcl$ and S91 and dummy	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 10:57
S10 8	2	bcl$ and S91 and ((sacrific$6 or test or blank) near (wafer or substrate))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 11:04
S10 9	2058	activat$3 with clean$3 with gas	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 11:04
S11 0	28	S109 and S91	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 11:04
S11 1	8	clean same ((bcl$ with (ar or argon)) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 15:58
S11 2	6	S91 and ((NF$6 with (ar or argon)) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 11:48
S11 5	1895	curtain near gas	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 12:41
S11 6	61	S91 and S115	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 13:07
S12 4	24	((deposit$3 with chamber) same (rf or (radio frequency)) same clean) and S91	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 13:48
S12 6	109	plasma with etch$6 with dummy (substrate or wafer) with clean$6	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 14:42
S12 7	84	S126 and cvd	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 15:28

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S13 2	83	((protect$6 or prevent$6) with (dummy wafer) with (block or wafer or substrate or chuck or susceptor) with clean$6 with (plasma or rf or (radio frequency))) and cvd and (heat$6 with (block or chuck or susceptor))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 15:39
S13 4	3	(clean$6 same S91 same (rf or (radio frequency))) and (heat$6 with (block or chuck or susceptor))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:01
S13 5	35	(clean$6 same (rf or (radio frequency))) and (heat$6 with (block or chuck or susceptor)) and S91	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:10
S13 6	197	(shower$1head or (shower head)) with first with second with hole	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:10
S13 7	92	((shower$1head or (shower head)) with first with second with hole) and (ald or cvd)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:11
S13 8	85	((shower$1head or (shower head)) with first with second with hole) and (ald or cvd) and (heat$6 with (substrate or wafer or chuck or block or susceptor))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:44
S14 1	2	((sacrific$6 or test or blank) (wafer or substrate)) same S91	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:46
S14 2	3	((dummy wafer) with (plasma or rf or (radio frequency)) with clean) and (heat$6 with (block or chuck or susceptor))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:50
S14 6	95	(((dummy wafer) with (plasma or rf or (radio frequency)) with clean$6) and (heat$6 with (block or chuck or susceptor)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:08
S14 7	7941	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:08
S14 8	3	(((dummy wafer) with (plasma or rf or (radio frequency)) with clean$6) and (heat$6 with (block or chuck or susceptor))) and S147	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:12

EAST Search History

S14 9	0	((((test or blank or sacrfic$6) near (substrate or wafer)) with (plasma or rf or (radio frequency)) with clean$6) and (heat$6 with (block or chuck or susceptor))) and S147	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:13
S15 0	2	((((test or blank or sacrfic$6 or dummy) near (substrate or wafer)) with (plasma or rf or (radio frequency)) with clean$6) and (heat$6 with (block or chuck or susceptor))) and ((curtain or (deposition control$6) or confinement) near gas)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:53
S15 1	0	((in$1situ or (in situ)) with clean$6) same (rf or (radio frequency)) same ((dummy or blank or test or sacrific$6) with (wafer or substrate))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:55
S15 2	5	((in$1situ or (in situ)) with clean$6) same (rf or (radio frequency) or plasma) same ((dummy or blank or test or sacrific$6) with (wafer or substrate))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:55
S15 3	49	("4924890" | "4936329" | "5014217").PN. OR ("5314509"). URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/28 09:06
S15 4	64	134/1.1.ccls. and dummy	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 11:28
S15 5	23	S147 and (first with second with hole with (shower$1head or (shower head)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 11:38
S15 6	4	("5567243"|"5595606").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 11:39
S15 8	87	("4209357" | "4625678" | "4951603" | "5252131").PN. OR ("5595606"). URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/28 11:43
S15 9	15	S158 and S147	USPAT	ADJ	ON	2006/04/28 15:42
S16 0	7941	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 15:44

EAST Search History

S16 4	69	S160 and (((in$1situ or (in situ)) with clean$6) same (rf or (radio frequency) or plasma))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 16:09
S16 6	247	S160 and (((chamber or reactor) with clean$6) same (rf or (radio frequency) or plasma))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 16:49
S16 7	36	S160 and (((chamber or reactor) with clean$6) same (ion))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 16:59
S16 8	57	S160 and clean$6.ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:00
S16 9	18	S160 and clean$6.ti. and (rf or (radio frequency))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:03
S17 0	114	("20020029747"|"20030019428"|"20030029566"|"20030038127"|"20030072639"|"20030079686"|"20030116087"|"20030129106"|"20030132319"|"20030221780"|"20040069225"|"20040070346"|"20040219789"|"20050205110"|"20050218507"|"20050221552"|"20050230350"|"4209357"|"4579618"|"4585920"|"4872947"|"4886570"|"4892753"|"4951601"|"5000113"|"5030319"|"5186718"|"5198034"|"5228501"|"5231690"|"5238499"|"5328558"|"5345999"|"5451259"|"5500249"|"5516367"|"5800686"|"5844195"|"5846332"|"5855681"|"5856240"|"5885404"|"5951776"|"5993916"|"6083344"|"6086677"|"6176198"|"6238513"|"6350320"|"6364949"|"6364954"|"6446572"|"6544340"|"6603269"|"6638810"|"6656831"|"6679981"|"6740585"|"6878206").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:04
S17 1	39	S170 and clean$6 same (plasma or rf or (radio frequency))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:05
S17 2	8	S170 and (clean$6 same (plasma or rf or (radio frequency))) and S160	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:16

EAST Search History

S17 3	244	S160 and ((ar or argon or nitrogen or "n.sub.2") with clean$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:16
S17 4	75	S160 and ((ar or argon or nitrogen or "n.sub.2") with clean$6 with (reactor or chamber))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:21
S17 5	30	S160 and (ar or argon or nitrogen or "n.sub.2") and clean$6.ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:22
S17 6	20	S160 and ((ar or argon or nitrogen or "n.sub.2") same (plasma or rf or (radio frequency))) and clean$6.ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:22
S17 7	44	134/1.1.ccls. and (dummy wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 13:20
S17 8	17	134/1.1.ccls. and (ALD or (atomic layer))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 08:36
S17 9	299	134/1.1.ccls. and (CVD or (chemical layer))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 15:07
S18 0	642	clean$6 with (dummy (wafer or substrate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 15:38
S18 1	4	S180 with (shower$1head or (shower head))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 15:39
S18 2	18	(ald or (atomic layer)) and (residue with wall with (chamber or reactor))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 16:20

EAST Search History

S18 4	8	(ald or (atomic layer)) same (residue with wall)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 16:22
S18 5	51	(ald or (atomic layer)) and (residue with wall)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 16:25
S18 6	80	(ald or (atomic layer)) and clean$6. ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 08:58
S18 9	16	134/1.1.ccls. and (ALD or (atomic layer)) and clean$6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 08:36
S19 0	32	(ald or (atomic layer)) with deposit$6 with residue	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 09:01
S19 1	1	("20040014327").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/02 09:01
S19 2	1	("20040180553").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/02 11:57
S19 4	0	(ALD or (atomic layer (deposition or epitaxy))) with (pre$1coat or (pre coat))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 15:19
S19 6	245	((ALD or (atomic layer (deposition or epitaxy))) with film with deposit$6) same (("Al.sub.2O.sub.3" or "HfO.sub.2" or "ZrO.sub.2." or alumina) with (deposit$6 or film or layer))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 12:10
S19 7	200	427/248.1 and ((ALD or (atomic layer (deposition or epitaxy))) with film with deposit$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 12:10
S19 8	16	427/248.1 and (((ALD or (atomic layer (deposition or epitaxy))) with film with deposit$6) same (("Al.sub. 2O.sub.3" or "HfO.sub.2" or "ZrO. sub.2." or alumina) with (deposit$6 or film or layer)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 12:22

S19 9	2	(ALD or (atomic layer (deposition or epitaxy))) same (pre$1coat or (pre coat))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 12:23
S20 0	1	("20030165620").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/02 15:13
S20 1	20	("4960488"|"5338363"|"5522934"|" 5670218"|"5988187"|"6183563"|"62 17658"|"6573184"|"6579372"|"6626 185").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 15:19
S20 3	4	(ALD or (atomic layer (deposition or epitaxy))) and ((clean$6 near gas) same bcl$)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 15:21
S20 4	75	(ALD or (atomic layer (deposition or epitaxy))) and ((plasma or rf or (radio frequency)) same bcl$)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 15:23
S20 5	24	(ALD or (atomic layer (deposition or epitaxy))) and ((plasma or rf or (radio frequency)) same bcl$ same clean$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/03 10:57
S20 6	11	(ALD or (atomic layer (deposition or epitaxy))) and ((shower$1head or (shower head)) with (isolat$6 or insulat$6) with electric$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/03 11:26
S20 7	1	("6886491").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/03 11:17
S20 8	1	("20020129769").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/03 11:17
S20 9	147	(cvd or (chemical vapor deposition)) and ((shower$1head or (shower head)) with (isolat$6 or insulat$6) with electric$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/03 11:28
S21 0	1	("6079356").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/03 11:28
S21 1	1	("20020007790").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/09 16:33